

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 6,891,593 B2  
DATED : May 10, 2005  
INVENTOR(S) : Kiyoshi Arakawa

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title page,

Item [56], **References Cited**, OTHER PUBLICATIONS,

"Okabe, Hideo. "Photochemistry of Small Molecules," *A Wiley-Interscience Publication*, 1978, p. 178." should read

-- Okabe, Hideo. "Photochemistry of Small Molecules," *A Wiley-Interscience Publication*, 1978, p. 178. --.

Item [57], **ABSTRACT**, replace with the following:

-- An exposure apparatus includes a reticle stage which holds a reticle, a projection optical system which projects a pattern of the reticle onto a substrate, and a reticle surface plate, which is a base plate disposed between the reticle and the projection optical system and which supports the reticle stage. The reticle surface plate has an opening for transmitting exposure light. The exposure apparatus further includes a sheet glass set on the reticle surface plate so as to separate a space inside the opening of the reticle surface plate from a space above the reticle surface plate. --.

Column 1,

Line 37, "recently" should be deleted.

Line 39, "have" should read -- have recently --.

Line 57, "cm" should read --  $\text{cm}^{-1}$ . --.

Line 58, "." should be deleted.

Column 2,

Line 42, the first occurrence of "an" should read -- and --.

Column 6,

Line 12, "&" should read -- and --.

Column 7,

Line 66, "inert" should read -- an inert --.

Column 8,

Line 12, "in the" should read -- on the --.

Line 47, "&" should read -- and --.

Column 10,

Line 20, "like" should read -- as in --.

Column 11,

Line 27, "as." should read -- gas. --.

Following line 37, insert as a new paragraph -- <Embodiment of Semiconductor Production System> --.

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Column 11 (cont'd),

Line 40, "micromachine" should read -- micromachine, --.

Line 56, the first occurrence of "apparatus," should read -- apparatus, a planarization apparatus, and the like) and post-process apparatuses (assembly apparatus, --.

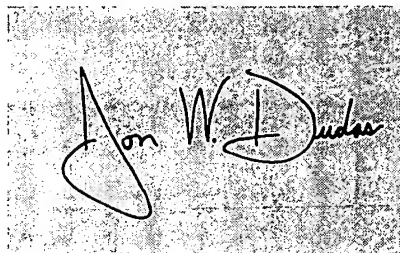
Column 14,

Line 21, "prevents a" should read -- prevents --.

Line 30, the second occurrence of "beam" should read -- beam. A sufficient transmittance and stability of the ArF excimer laser beam or fluorine (F<sub>2</sub>) excimer laser beam --.

Signed and Sealed this

Twenty-seventh Day of December, 2005

A handwritten signature in black ink, reading "Jon W. Dudas", is written over a rectangular area with a textured, grey background.

JON W. DUDAS

*Director of the United States Patent and Trademark Office*